

SPUTTERING TARGET FOR MAGNETIC RECORDING MEDIUM,
AND MAGNETIC THIN FILM

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ABSTRACT

10 A sputtering target or a film containing 0.1 to 10 mol% of an oxide of one or more types of elements selected from Ca, K, Na, Pb, and Zn, 45 mol% or less of Cr, 45 mol% or less of Pt, and remainder being Co. An object of the present invention is to provide a sputtering target capable of considerably reducing the particles caused by oxides and significantly improving the yield during deposition. It is thereby possible to deposit a quality magnetic recording layer and improve the yield of a magnetic recording medium.

15 Fig. 1